

What is claimed is:

1. A method of manufacturing a light-transmitting electromagnetic wave-shielding material comprising:

- (A) forming a hydrophilic transparent resin layer on a transparent substrate;
- (B) forming an electroless plating layer on the hydrophilic transparent resin layer so that the hydrophilic transparent resin layer is blackened when seen from its rear side;
- (C) forming an electroplating layer on the electroless plating layer;
- (D) forming a resist section in a desired pattern on the electroless plating layer;
- (E) performing etching to remove the electroless electroplating layer and the electroplating layer on a non-resist section, where the resist section is not formed, of the electroplating layer, while patterning in black the hydrophilic transparent resin layer under the electroless plating layer when seen from its rear side;
- (F) removing the resist section on the electroless plating layer from the electroless plating layer; and
- (G) forming a black electroplating layer covering the electroplating layer and the electroless plating layer.

2. A method of manufacturing a light-transmitting electromagnetic wave-shielding material comprising:

- (A) forming a hydrophilic transparent resin layer on a transparent substrate;
- (B) forming an electroless plating layer on the hydrophilic transparent resin layer so that the hydrophilic transparent resin layer is blackened when seen from its rear side;
- (C) forming a resist section in a desired pattern on the electroless plating layer;
- (D) performing etching to remove a non-resist section of the electroless plating layer, on which the resist section is not formed, while patterning in black the hydrophilic transparent resin layer under the electroless plating layer when seen from its rear side;
- (E) removing the resist section on the electroless plating layer from the electroless plating layer;
- (F) forming an electroplating layer on the electroless plating layer; and

(G) forming a black electroplating layer covering the electroplating layer and the electroless plating layer.

3. A method of manufacturing a light-transmitting electromagnetic wave-shielding material comprising:

- (A) forming a hydrophilic transparent resin layer on an entire surface of a transparent substrate;
- (B) forming an electroless plating layer on an entire surface of the hydrophilic transparent resin layer so that the hydrophilic transparent resin layer is blackened when seen from its rear side;
- (C) forming a resist section in a desired pattern on the electroless plating layer;
- (D) forming an electroplating layer on a non-resist section of the electroless plating layer, on which the resist section is not formed;
- (E) removing the resist section on the electroless plating layer from the electroless plating layer;
- (F) performing etching to remove an electroplating layer non-existent portion of the electroless plating layer while patterning in black the hydrophilic transparent resin layer under the electroless plating layer when seen from its rear side; and
- (G) forming a black electroplating layer covering the electroplating layer and the electroless plating layer.

4. A method of manufacturing a light-transmitting electromagnetic wave-shielding material comprising:

- (A) forming a hydrophilic transparent resin layer on a transparent substrate;
- (B) forming an electroless plating layer on the hydrophilic transparent resin layer so that the hydrophilic transparent resin layer is blackened when seen from its rear side;
- (C) forming an electroplating layer on the electroless plating layer;
- (D) forming a black electroplating layer on the electroless plating layer;
- (E) forming a resist section in a desired pattern on the black electroplating layer; and
- (F) performing etching to remove a non-resist section of the black electroplating layer, on

which the resist section is not formed, while patterning in black the hydrophilic transparent resin layer under the electroless plating layer when seen from its rear side, and then removing the resist section on the black electroplating layer from the black electroplating layer.

5. A method of manufacturing a light-transmitting electromagnetic wave-shielding material, wherein the black electroplating layer in Claim 1 is constituted by a nickel, chromium, tin, rhodium, or ruthenium metal or an alloy of any of these.

6. The light-transmitting electromagnetic wave-shielding material manufactured by the method of manufacturing the light-transmitting electromagnetic wave-shielding material according to Claim 1.

7. A method of manufacturing a light-transmitting electromagnetic wave-shielding material, wherein the black electroplating layer in Claim 2 is constituted by a nickel, chromium, tin, rhodium, or ruthenium metal or an alloy of any of these.

8. A method of manufacturing a light-transmitting electromagnetic wave-shielding material, wherein the black electroplating layer in Claim 3 is constituted by a nickel, chromium, tin, rhodium, or ruthenium metal or an alloy of any of these.

9. A method of manufacturing a light-transmitting electromagnetic wave-shielding material, wherein the black electroplating layer in Claim 4 is constituted by a nickel, chromium, tin, rhodium, or ruthenium metal or an alloy of any of these.